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(54) Title: WELL PLATE SUPPORT

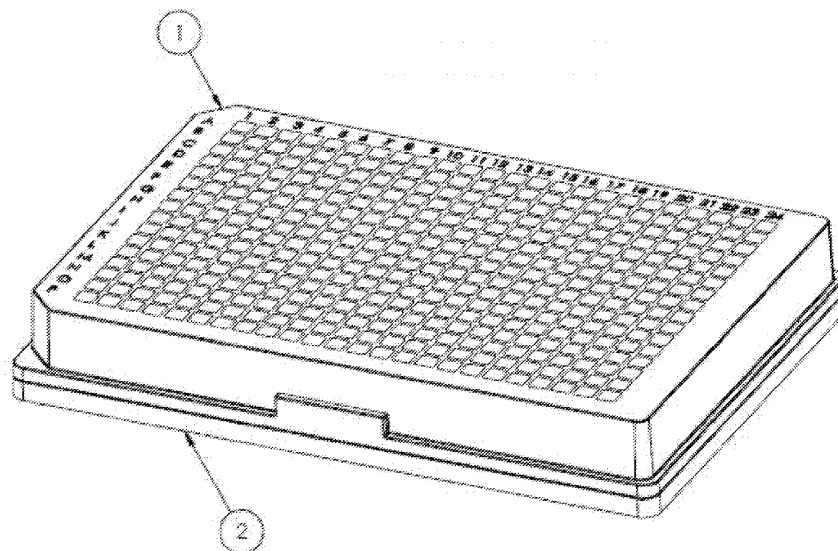


FIG. 1

(57) Abstract: A support for a well plate, the support comprising: a tiered rectangular structure comprising at least a top level and a lower level; a length and a width of the top level being less than a length and a width of the lower level, and the length and the width of the top level being at least the same as a length and a width of an optical read surface of the well plate; and the length and width of the lower level being greater than the length and the width of the top level, and the length and the width of the lower level are at least the same as a length and a width of the well plate. The disclosure herein relates to a support to prevent deformation of a well plate during centrifugation. In some embodiments, the support comprises tiered levels to ensure the well plate does not continuously make physically contact with the support.

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